



"WBG semiconductor simulation technology"

Date and time: Friday, May 19, 2023 13:00-17:35

Location: Kikai Shinko Kaikan 6-67 Conference Room

3-5-8 Shiba Koen, Minato-ku, Tokyo

Simulations in Si device	ce and process development have high calculation accu	rracy, and can be used for prototyping in research and development.
The importance of a	Iternative simulations is increasing. On the	other hand, in the simulation of WBG material system,
Physical property pa	arameters and physical models are not fully	reflected and are not fully utilized as EDA.
There is a current situation	n. Therefore, in this discussion, we will discuss to what ex	tent WBG semiconductor simulation technology is currently available.
We will discuss mod	lel parameters, computational issues, and fu	uture prospects.
progra	m	
12:30	venue	
13:00-13:10 Openin	ng remarks, explanation of today's	
progress [Part 1] P	resentation and	
discussion of SiC to	opics 13:10-13:40 Physical model of SiC p	hysical
		properties in TCAD Tetsuo Hatakeyama
(Toyama Prefectura	al University) 13:40-14:00 Development of	ultra-high voltage
		SiC IGBT using TCAD Naoki Watanabe (Hitachi,
14:00-14:40 Individ	dual discussion on SiC Break	
[Part 2]	14:40-14:50)
Presentation and c	discussion of GaN topics	
14:50-15:10 Challe	enges of TCAD simulation in GaN-HEMT	Akira Nakajima (Industrial
		National Institute of Technology)
15:10ÿ15:30 Progress a	and prospects of high-field physical property evaluati	on of GaN
		Takuya Maeda (University of Tokyo)
15:30ÿ15:40 Reverse bi	as leakage current simulation in dislocation-free Ga	N pn junction
	GaN	Tomoyuki Shoji (Toyota Central Research Institute)
analysis 15:40-16:2	20 Individual discussion on	
16:20-16:30	GaN Break	
[Part 3] Participant	s provide topics and general discussion	
16:30-17:30 Partic	ipants also provide information Discussio	n based
	on the above questions Q&A/	
discussion through	out 17:30-17:35 Closing remarks	

ÿAbout Participation: This is a discussion group where everyone can participate to discuss WBG semiconductor simulation technology. participant The chairperson may ask you to speak. When doing so, be sure to speak up (if you are having trouble with the simulation).

Please leave any comments you may have, such as what you are doing or any questions you may have. We welcome comments using slides.

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ÿParticipation registration: Please register your participation using the web participation registration system (click here). Deadline: April 24th (Monday). Main idea If the text inside is printed, https://formok.com/f/zs5r56x9 Please access more.

ÿParticipation fee: (tax included) After applying for participation, we will inform you about online payment.

Advanced Power Semiconductor Subcommittee members* 2,000 yen, general public 4,000 yen, students (subcommittee members/general) 1,000 yen

*We will notify you where to download the proceedings (PDF) on Friday, May 12th. No refunds will be accepted after this time.

ÿPlease cooperate with the on-site event: If you have a fever, please refrain from participating on the day of the event. Masks at the venue Wearing is optional.

ÿContact information:

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